## Sialon-based oxynitride phosphor, process for its production, and use thereof

Patent number:

EP1445295 2004-08-11

Also published as:

Cited documents:

**Publication date:** 

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**区 US2004155225 (A1)** 

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Classification:

- international:

C09K11/08; C09K11/77; H01L33/00; C09K11/08; C09K11/77; H01L33/00; (IPC1-7); C09K11/08; C04B35/00; C09K11/77; H01L33/00; H05B33/14

- european:

Application number: EP20040002508 20040205 Priority number(s): JP20030029274 20030206; JP20030029277 20030206

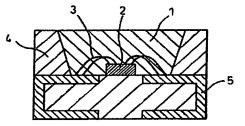
C09K11/08J; C09K11/77D; C09K11/77M6; C09K11/77N6; C09K11/77P6; C09K11/77S6

EP1278250 EP1264873 XP001151981 XP004215129

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## Abstract of EP1445295

An alpha -sialon-based oxynitride phosphor characterized in that the content of alpha -sialon An appra-station-based oxynutride pricesprior craracterized in that the content of appra-station represented by the general formula: MxSi12-(m+n)Al(m+n)OnN16-ni.Lny (wherein M is at least one metal selected from among Li, Ca, Mg, Y or lanthanide metals excluding La and Ce, Ln is at least one lanthanide metal selected from among Ce, Pr and La or at least one lanthanide metal selected from among Eu, Dy, Er, Tb and Yb, 0.3 < x + y < 1.5, 0 < x < 0.7, 0.3 < x < 0.7, 0.3 < x < 0.7, and 0.7, 0.7 or 0.7, of the metal M dissolved in the alpha-sialon is replaced with the lanthanide metal Ln, wherein an of a ponding the luminescence center, is 75 wt% or greater when the lanthanide metal Ln is at least one lanthanide metal selected from among Ce, Pr and La and 90 wt% or greater when the lanthanide metal Ln is at least one lanthanide metal selected from among Eu, Dy, Er, Tb and Yb, and in that the content of metal impurities other than the metal M, lanthanide metal Ln, silicon, IIIA elements (aluminum, gallium), oxygen and nitrogen, is no greater than 0.01 wt%.



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